





AC microLine[®] 2000-P⁴

PRIME WAFER DOUBLE-SIDE POLISHING SYSTEM



THE MOST COMPREHENSIVE SOLUTION



Unique LPAC (Lower Platen Adaptive Control) System (patent pending)



Unique and patented UPAC (Upper Platen Adaptive Control) System



3 Gap Sensors



Benchmark in precision, quality, efficiency, and cost of ownership

PUSHING THE LIMITS

enhancing surface quality

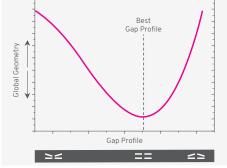




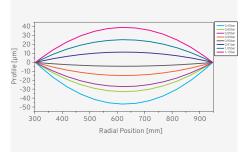
HIGHLIGHTS AC microLine® 2000-P⁴

- Unique and patented UPAC (Upper Platen Adaptive Control) System
- Unique LPAC (Lower Platen Adaptive Control) System (patent pending)
- Monitoring of the cooling lubricant flow rate
- Loop control
- First-Class customer support for the highest machine availability and productivity
- Integrated high precision interferometric device for in-situ measurement of the wafer thickness
- High-Pressure Conditioner

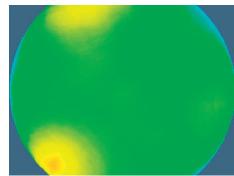
- Slurry Recycling Station
- Slurry Pressure Distribution
- Integrated Process Data Recording (DataCare[®])
- Industry 4.0
- Touch Screen



The importance of the gap – Perfect wafer flatness requires gap adjustment



LPAC System – Radial Measurement



GBIR < 100 nm / SBIR < 40 nm SFQR < 20 nm / ESFQR < 60 nm

TECHNICAL DATA	AC microLine® 2000-P ⁴
Wheel diameter [mm]	1935
Ring width [mm]	686
Max. load pressure [daN]	4000
Upper/lower drive power [kW]	46
Upper/lower drive speed [rpm]	0-40
Center drive power [kW]	7.5
Center drive speed [rpm]	0-50
Outer drive power [kW]	9.5
Outer drive speed [rpm]	0-7.5
Working wheel cooling	Labyrinth
Dimensions [H×W×D] [mm]	3000×4200×3900
Weight [kg]	21000
Load capacity 300 mm [12"] Wafer 200 mm [8"] Wafer	15 pieces 30 pieces

GET IN TOUCH WITH US TODAY TOGETHER WE WILL FIND A SOLUTION FOR YOUR REQUIREMENTS

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